

## CLAIM AMENDMENTS

Please amend the claims as described below. In accordance with 37 CFR §1.121, a complete listing of all claims in the application is provided below. Notably, the status of each claim is indicated in the parenthetical expression adjacent to the corresponding claim number.

Claims 1-35 **(Canceled)**.

1        36. **(Currently Amended)** An electromechanical device comprising:  
2        a substrate;  
3        a mechanical structure disposed over the substrate wherein a monolayer or self-  
4 assembled layer is disposed on at least a portion of the mechanical structure;  
5        a film encapsulation structure, disposed over the mechanical structure, to ~~define and~~  
6 seal a chamber;  
7        an anti-stiction channel, etched into the film encapsulation structure, to provide  
8 access to at least a portion of the mechanical structure disposed in the chamber; and  
9        an anti-stiction plug, disposed over or in the anti-stiction channel, to re-seal the  
10 chamber.

1        37. **(Previously Presented)** The device of claim 36 wherein the film encapsulation  
2 structure includes first and second encapsulation layers.

1        38. **(Previously Presented)** The device of claim 37 wherein the first encapsulation  
2 layer includes polycrystalline silicon, porous polycrystalline silicon, amorphous silicon,  
3 silicon carbide, silicon nitride, silicon/germanium, germanium, or gallium arsenide.

1           39. **(Previously Presented)** The device of claim 37 wherein the second  
2 encapsulation layer includes polycrystalline silicon, porous polycrystalline silicon,  
3 amorphous silicon, germanium, silicon/germanium, gallium arsenide, or silicon carbide.

1           40. **(Previously Presented)** The device of claim 36 wherein the anti-stiction plug  
2 includes spin-on polymer, SOG or a metal material.

1           41. **(Previously Presented)** The device of claim 36 wherein the anti-stiction plug  
2 includes spin-on polymer or SOG which is deposited using silk screening.

1           42. **(Previously Presented)** The device of claim 36 wherein the anti-stiction plug  
2 includes spin-on polymer or SOG which is deposited using dispensed seal-glass, plastic  
3 and/or epoxy.

1           43. **(Previously Presented)** The device of claim 36 wherein the anti-stiction plug is  
2 deposited using a shadow mask technology.

1           44. **(Previously Presented)** The device of claim 36 further including a trap,  
2 disposed between the anti-stiction channel and the mechanical structure.

1           45. **(Previously Presented)** The device of claim 44 wherein the trap is a  
2 substantially vertical trap.

1           46. **(Previously Presented)** The device of claim 44 wherein the trap is a  
2 substantially horizontal trap.

1           47. **(Previously Presented)** The device of claim 36 further including a diffusion  
2 barrier disposed over the anti-stiction plug.

1           48. **(Previously Presented)** The device of claim 47 wherein the diffusion barrier  
2 includes a metal material.

Claims 49-62 **(Canceled)**.

1           63. **(Currently Amended)** An electromechanical device comprising:  
2 a substrate;  
3 a mechanical structure disposed over the substrate wherein an anti-stiction layer is  
4 disposed on at least a portion of the mechanical structure;  
5 a film encapsulation structure, disposed over the mechanical structure, to define in  
6 part, a chamber;  
7 an anti-stiction channel, formed in the film encapsulation structure, to allow the anti-  
8 stiction layer to be disposed on at least the portion of the mechanical structure disposed in  
9 the chamber; and  
10 an anti-stiction plug, disposed over or in the anti-stiction channel, to re-seal the  
11 chamber.

1           64. **(Previously Presented)** The device of claim 63 wherein the film encapsulation  
2 structure includes first and second encapsulation layers.

1           65. **(Previously Presented)** The device of claim 64 wherein the first encapsulation  
2 layer includes polycrystalline silicon, porous polycrystalline silicon, amorphous silicon,  
3 silicon carbide, silicon nitride, silicon/germanium, germanium, or gallium arsenide.

1           66. **(Previously Presented)** The device of claim 64 wherein the second  
2 encapsulation layer includes polycrystalline silicon, porous polycrystalline silicon,  
3 amorphous silicon, germanium, silicon/germanium, gallium arsenide, or silicon carbide.

1           67. **(Previously Presented)** The device of claim 63 wherein the anti-stiction plug  
2 includes spin-on polymer, SOG or a metal material.

1           68. **(Previously Presented)** The device of claim 63 wherein the anti-stiction plug  
2 includes spin-on polymer or SOG which is deposited using silk screening.

1           69. **(Previously Presented)** The device of claim 63 wherein the anti-stiction plug  
2 includes spin-on polymer or SOG which is deposited using dispensed seal-glass, plastic  
3 and/or epoxy.

1           70. **(Previously Presented)** The device of claim 63 wherein the anti-stiction plug is  
2 deposited using a shadow mask technology.

1           71. **(Previously Presented)** The device of claim 63 further including a trap,  
2 disposed between the anti-stiction channel and the mechanical structure.

1           72. **(Previously Presented)** The device of claim 71 wherein the trap is a  
2 substantially vertical trap.

1           73. **(Previously Presented)** The device of claim 71 wherein the trap is a  
2 substantially horizontal trap.

1           74. **(Previously Presented)** The device of claim 71 wherein the trap includes a  
2 substantially horizontal portion and a substantially vertical portion.

1           75. **(Previously Presented)** The device of claim 63 further including a diffusion  
2 barrier disposed over the anti-stiction plug.

1           76. **(Previously Presented)** The device of claim 75 wherein the diffusion barrier is  
2 a metal layer.

1           77. **(Previously Presented)** The device of claim 63 wherein the anti-stiction layer  
2 is a monolayer or self-assembled layer.